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NEWS RELEASE

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For Immediate Release

Gelest Offers New Silicon Precursors for Silicon Nitride Ultrathin Film Deposition

Establishes new thin film deposition application lab for proof of concept research and joint development projects

MORRISVILLE, Pa. (June 25, 2019) – Gelest, Inc., a leading innovator in materials science and a New Mountain Capital portfolio company, today introduced new silicon source precursors for silicon nitride (SiN) ultrathin film deposition in semiconductor applications. Gelest supports these new precursors with film deposition and process data from its newly established thin film applications lab.

Silicon Nitride (SiN) thin films have broad utility in integrated circuitry (IC) applications due to their combination of physical, mechanical, electrical, and optoelectronic properties. These films are used in microprocessor units (MPU), system-on-a-chip (SoC), flash memory, and three-dimensional integrated circuits (3D IC).

There is an increasing demand for new and commercially available SiN precursors for a variety of deposition processes, especially those requiring a low thermal budget.

“As a vertically-integrated leader in the synthesis, manufacturing, and supply of precursors for SiN, we have further extended our precursor offering in four major

categories, perhydridosilanes, hydridohalosilanes, halosilanes, and aminosilanes ” said Dr. Jeffrey T. DePinto, Business Manager.

Gelest’s precursors are designed with desirable combinations of physical properties, thermal stability and chemical reactivity to meet the needs of SiN deposition processes involving chemical vapor deposition (CVD), plasma enhanced CVD (PE CVD), atomic layer deposition (ALD), and liquid phase deposition (LPD).

“We are fully committed to enabling the industry to accelerate the adoption of SiN ultrathin film technology, as well as the next generation cobalt ultrathin metallization film technology. To that that end, we built a thin film deposition application lab in our R&D center in Pennsylvania for proof of concept research and joint development projects with our customers,” said Dr. DePinto.

To learn more about silicon source precursors for SiN ultrathin film deposition, please email info@gelest.com. To view a complete listing of precursors for SiN, please visit Gelest.com.

About Gelest

Gelest, Inc., headquartered in Morrisville, Pennsylvania, is an innovator, manufacturer, and supplier of silicones, organosilanes, metal-organics, and surface-treated pigments for advanced technology end markets including medical device, life sciences, microelectronics, personal care, and advanced coatings, adhesives, sealants, elastomers (CASE) markets. The company helps customers succeed by assisting them in the development and supply of chemistry to solve their most challenging materials science problems and enable their new product technology.

www.gelest.com

About New Mountain Capital

New Mountain Capital is a New York based investment firm that emphasizes business building and growth, rather than debt, as it pursues long-term capital appreciation. The firm currently manages private equity, public equity, and credit funds with over \$20 billion in assets under management. New Mountain seeks out what it believes to be the highest quality growth leaders in carefully selected industry sectors and then works intensively with management to build the value of these companies.

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